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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/601,195	06/23/2003	Jaung-Joo Kim	SEC.1013	6419
20987	7590	05/31/2006	EXAMINER	
VOLENTINE FRANCOS, & WHITT PLLC ONE FREEDOM SQUARE 11951 FREEDOM DRIVE SUITE 1260 RESTON, VA 20190			EL ARINI, ZEINAB	
			ART UNIT	PAPER NUMBER
			1746	

DATE MAILED: 05/31/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary	Application No.	Applicant(s)	
	10/601,195	KIM ET AL.	
	Examiner	Art Unit	
	Zeinab E. EL-Arini	1746	

– The MAILING DATE of this communication appears on the cover sheet with the correspondence address –
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) Responsive to communication(s) filed on 22 March 2006.
- 2a) This action is FINAL. 2b) This action is non-final.
- 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) Claim(s) 6-25 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) Claim(s) _____ is/are allowed.
- 6) Claim(s) 6-25 is/are rejected.
- 7) Claim(s) _____ is/are objected to.
- 8) Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) The specification is objected to by the Examiner.
- 10) The drawing(s) filed on _____ is/are: a) accepted or b) objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) All b) Some * c) None of:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. _____.
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- 1) Notice of References Cited (PTO-892)
- 2) Notice of Draftsperson's Patent Drawing Review (PTO-948)
- 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
Paper No(s)/Mail Date _____.
- 4) Interview Summary (PTO-413)
Paper No(s)/Mail Date. _____.
- 5) Notice of Informal Patent Application (PTO-152)
- 6) Other: _____.

DETAILED ACTION

The amendment and remarks filed 03/22/06 have been acknowledged and entered.

Claim Rejections - 35 USC § 103

1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

2. Claims 6-25 are rejected under 35 U.S.C. 103(a) as being unpatentable over Torii et al. (5,972,862) in combination with Tan (6,810,887) and Hightower et al. (3,033,710) and Maruyama et al. (5,962,385).

3. This rejection stated in paper No. 012006 has been withdrawn in view of applicants' amendment and remarks.

4. Claims 6-25 are rejected under 35 U.S.C. 103(a) as being unpatentable over Maruyama et al. (5,962,385) in combination with Segawa et al. (US 2002/007886 A1)(new reference), Tan (6,810,887) and Hightower et al. (3,033,710) .

Maruyama et al. disclose a method and cleaning liquid for cleaning semiconductor device. The reference discloses dipping the semiconductor device in cleaning solution comprising the fluoric salt, the organic solvent, and water, and rinsing the device. See col. 2, line 45- col. 3, line 48. The reference discloses examples of the inorganic substrate to which the cleaning liquid is applied include semiconductor wiring materials,

Art Unit: 1746

such as silicon, ----; compound semiconductors, ----, and glass substrates, such as LCD. See col. 3, line 57- col. 4, line 2.

Maruyama et al. as discussed supra discloses all limitations with the exception of the organic acid, treating the ceramic parts with heat, the concentration, dipping the parts in the alkali solution and the time as claimed.

5. Segawa et al. disclose a method of treating ceramic parts of the semiconductor fabrication equipment. The reference discloses treating the surface with a solution comprises ammonium fluoride and organic acid as claimed. See the abstract, paragraphs 11, 14-15, 17, and example 2.

6. It would have been obvious for one skilled in the art to use the organic acid taught by Segawa et al. in the Maruyama et al. process to obtain the claimed process. This is because both references are from the same technical endeavor, which is cleaning ceramic parts by using a solution comprises ammonium fluoride and organic solvent.

Tan discloses a method for cleaning semiconductor fabrication equipment parts comprising cleaning the parts with HF/HNO₃ cleaning bath, rinsing the parts, and treating the parts with heat to remove the moisture from the parts. The reference discloses using the ultrasonic as claimed. See the claims, col. 12, lines 7-53.

It would have been obvious for one skilled in the art to use the ultrasonic and the heating step taught by Tan in the Maruyama et al. process to remove any moisture from the parts and to improve the cleaning process.

Maruyama et al. in combination with Segawa et al. and Tan do not teach dipping the parts in the basic solution as claimed.

Hightower et al. disclose a method for cleaning objects comprising treating the object in a first bath comprises acid solution, and then immersing the articles in a second bath containing alkaline solution. The reference teaches cleaning the ceramic parts, and using the sodium hydroxide as claimed. See claim 18. See also claims 3, 5, 8, and 22.

It would have been obvious for one skilled in the art to use the alkaline solution taught by Hightower et al in the Maruyama et al. in combination with Segawa et al. and Tan process to neutralize any acid solution adheres to the parts.

It would have been obvious for one skilled in the art to adjust the concentration, and the time to obtain optimum results.

Response to Arguments

7. Applicant's arguments filed 3/22/06 have been fully considered but they are not persuasive. Applicants' argument with respect to Maruyama et al, Segawa et al. and Hightower et al. do not teach cleaning ceramic parts is unpersuasive. This is because Segawa et al. disclose after machining, particles attached are removed by washing, the silica glass jig (ceramic part) is repeatedly immersed in a treating solution containing ammonium fluoride, organic acid and water. See paragraph 15. With respect to Maruyama et al, see col. 3, lines 57-col. 4, line 2, and with respect to Hightower et al, see claim 18.

Conclusion

8. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Yamaguchi et al. (6,855,576) disclose method for cleaning a ceramic member for use in a system for producing semiconductors, a cleaning agent and a combination of cleaning agents.

9. **THIS ACTION IS MADE FINAL.** Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Zeinab E. EL-Arini whose telephone number is (571) 272-1301. The examiner can normally be reached on Monday-Friday.

Art Unit: 1746

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Barr can be reached on (571) 272-1414. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Zeinab E. EL-Arini
Zeinab E. EL-Arini
Primary Examiner
Art Unit 1746

ZEE
05/25/06